

## Facile Conversion of Bis-Silylene to Cyclic Silylene Isomers: Unexpected C–N and C–H Bond Cleavage

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### Supporting Information

**ABSTRACT:** Reaction of thiolate **1** with carbene-stabilized diiodo-bis-silylene (**2**) (in a 2:1 ratio) in THF unexpectedly gives both the first five-membered, sulfur-containing, zwitterionic silylene ring (**3**) via insertion of the “ $\text{Si}^{\text{l}}_2$ ” unit of **2** into the olefinic C–H bond of the imidazole ring of **1** and four-membered cyclic silylene (**4**) via insertion of a silicon(I) atom of **2** into the  $\text{C}_{\text{phenyl}}\text{—N}$  bond of the carbene ligand. The parallel reaction in toluene only gives **3** as the major product. The nature of the bonding in isomeric **3** and **4** was probed by experimental and theoretical methods.

Silylenes ( $\text{R}_2\text{Si}:$ ), highly reactive divalent silicon species, are remarkable reaction intermediates.<sup>1–3</sup> In particular, the parent silylene ( $\text{H}_2\text{Si}:$ )<sup>4</sup> and chlorosilylenes<sup>5–7</sup> have been observed as reactive intermediates in chemical vapor deposition (CVD) of silicon from silane and chlorosilanes, respectively. Since the seminal discoveries of the siliconocene<sup>8</sup> and diamidosilylene,<sup>9</sup> a number of stable silylenes have been synthesized and employed in a variety of chemical processes including organic syntheses, transition-metal coordination, catalysis, and small-molecule activation.<sup>10–18</sup>

N-Heterocyclic silylenes have emerged as the most extensively studied cyclic silylenes (Figure 1a–c).<sup>9,19,20</sup> In

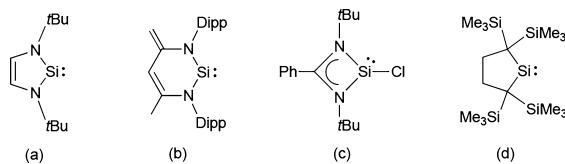


Figure 1. Representative cyclic silylenes.

contrast, cyclic alkyl silylenes (Figure 1d)<sup>21</sup> have been reported to be less persistent than those with stabilizing  $\pi$ -donor substituents. Acyclic silylenes are usually stabilized by Lewis base coordination.<sup>22</sup> Notably, stable, acyclic, two-coordinate silylenes have only recently been reported.<sup>23–27</sup> Among these acyclic two-coordinate silylenes, boryl(amino)silylene and diaminosilylene have been utilized in  $\text{H}_2$ ,  $\text{O}_2$ , and  $\text{NH}_3$  activations.<sup>26,27</sup>

This laboratory prepared an N-heterocyclic carbene (NHC)-stabilized bis-silylene [ $\text{L:(Cl)Si—Si(Cl):L}$ ] via  $\text{KC}_8$  reduction of  $\text{L:SiCl}_4$  [ $\text{L: = :C}\{\text{N(2,6-Pr}_2\text{C}_6\text{H}_3)\text{CH}\}_2$ ].<sup>28</sup> The synthesis of

[ $\text{L:(X)Si—Si(X):L}$ ,  $\text{X = Cl, Br, and I}$  (**2**)] by combining  $\text{L:Si=Si:L}$  [ $\text{L: = :C}\{\text{N(2,6-Pr}_2\text{C}_6\text{H}_3)\text{CH}\}_2$ ]<sup>28</sup> with 1,2-dihaloethanes was subsequently reported.<sup>29</sup> Reaction of dihalo(bis-silylenes) with anionic ligands may provide an efficient route to aggregate the bis-silylene moiety into a variety of organic and organometallic substrates, rendering unusual low-oxidation-state organosilicon species. Herein, we report thiolate (**1**)-mediated conversion of bis-silylene (**2**) to five- and four-membered cyclic silylene isomers (**3** and **4**) via unexpected C–H and C–N bond cleavage, respectively.<sup>30</sup> Compounds **3** and **4**, notably, are the first cyclic silylenes containing a silicon–silicon bond. Although silylenes have been reported to participate in C–H bond activation of various organic substrates,<sup>31–37</sup> Compound **3** represents the first “ $\text{Si}^{\text{l}}_2$ ” insertion into an olefinic C–H bond. Recently, main group species-mediated C–N bond activation of NHCs have begun to receive increased attention.<sup>38,39</sup> In addition to alkali metal-mediated C–N bond cleavage of saturated NHCs<sup>40,41</sup> and N-heterocyclic guanidine,<sup>42</sup> a series of main group (i.e., beryllium, silicon, boron, and aluminum) hydrides and Lewis acids have been reported to involve imidazole ring expansion reactions (RERs) via  $\text{C}_{\text{NHC}}\text{—N}$  bond activation.<sup>43–51</sup> Notably, reactive borylene intermediates have been proposed to insert into a  $\text{C}_{\text{phenyl}}\text{—N}$  bond of N-heterocyclic olefins.<sup>52</sup> To the best of our knowledge, **4** represents the first silicon(I)-mediated C–N bond cleavage of NHCs.

Recently, we synthesized an imidazole-based thiolate (**1**) by disulfurization of anionic N-heterocyclic dicarbene (Scheme 1).<sup>53</sup> Reaction of **1** with carbene-stabilized diiodo(bis-silylene) (**2**) in a 2:1 ratio in toluene gave **3** in 52.5% yield, whereas the parallel reaction in THF afforded a mixture containing cyclic silylene isomers **3** and **4** in a molar ratio of 7:1 (based on  $^1\text{H}$  NMR data) (Scheme 1). Compounds **3** and **4** may be isolated as yellow and colorless crystals, respectively. Notably, we did not observe the interconversion between isomeric **3** and **4**.

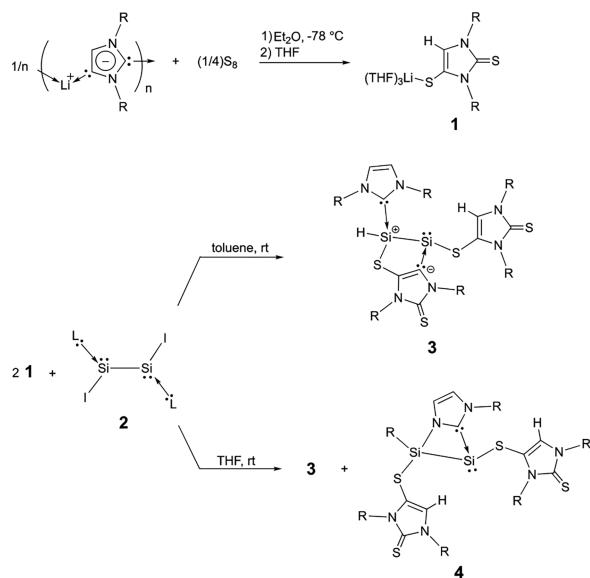
The core of **3** contains a five-membered silylene ring (Figure 2), which is achieved via the “ $\text{Si}^{\text{l}}_2$ ” insertion into the imidazole C–H bond of the complexed thiolate **1**. The  $\text{C}_2\text{Si}_2\text{S}$  ring in **3** (the  $\text{Si—S—C—C}$  torsion angle =  $-30.2^\circ$ ) is obviously bent, which may be due to the spatial repulsion between the bulky ligands in **3** (Figure S1).<sup>30</sup> Indeed, the doubling of the resonance of the NHC ring protons (7.98 and 8.06 ppm) of **3** may be attributed to the slow rotation of the  $\text{C}_{\text{NHC}}\text{—Si}$  bond,

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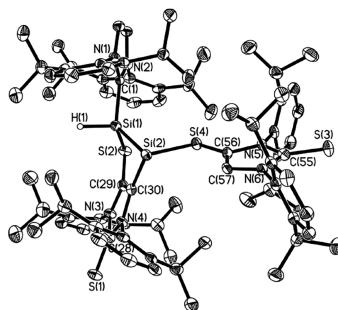
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**Scheme 1. Thiolate (1)-Mediated Conversion of Bis-Silylene (2) to Cyclic Silylene Isomers (3 and 4)<sup>a</sup>**

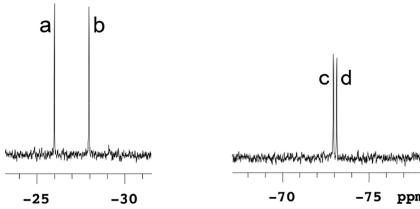


<sup>a</sup>[L: = :C{N(2,6-Pr<sup>i</sup><sub>2</sub>C<sub>6</sub>H<sub>3</sub>)CH}<sub>2</sub>; R = 2,6-Pr<sup>i</sup><sub>2</sub>C<sub>6</sub>H<sub>3</sub>].



**Figure 2.** Molecular structure of 3. Thermal ellipsoids represent 30% probability. Hydrogen atoms attached to the carbons have been omitted for clarity. Selected bond distances (Å) and angles (deg): Si(1)–H(1), 1.441(19); Si(1)–Si(2), 2.349(2); Si(1)–C(1), 1.909(6); Si(1)–S(2), 2.183(2); Si(2)–S(4), 2.263(2); Si(2)–C(30), 1.941(6); C(1)–Si(1)–Si(2), 123.89(18); S(2)–Si(1)–Si(2), 106.57(9); Si(1)–Si(2)–S(4), 93.40(8); Si(1)–Si(2)–C(30), 77.33(17).

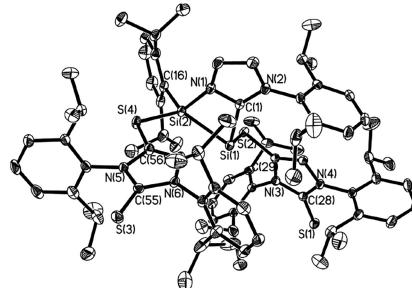
which is also caused by the steric bulk of the ligands.<sup>54</sup> The Si–Si bond distance for 3 [2.349(2) Å] is almost equal to the sum of silicon covalent radii (2.34 Å),<sup>55</sup> however, somewhat shorter than those [2.385(1)–2.393(3) Å] for [L:(X)Si–Si(X):L, X = Cl, Br, and I (2)]<sup>28,29</sup> and that (2.428 Å) for 3-Ph.<sup>30</sup> Natural bond orbital (NBO) analysis of 3-Ph indicates that the Si–Si  $\sigma$  bond (Figure S2) polarization is 64.4% toward Si(1) (32.7% s-, 67.1% p-, 0.2% d-character) and 35.6% toward Si(2) (8.6% s-, 90.7% p-, 0.7% d-character).<sup>30</sup> The Si(1) atom bears a positive charge of +0.63, while the C(30) atom bears a negative charge of −0.34. The H(1) atom bound to the four-coordinate Si(1) atom in 3 renders 4.61 ppm <sup>1</sup>H NMR resonance, which was located in the difference Fourier map. The Si–H coupling constants (<sup>1</sup>J<sub>Si–H</sub> = 195 Hz and <sup>2</sup>J<sub>Si–H</sub> = 20 Hz) shown in the proton-coupled <sup>29</sup>Si NMR spectrum of 3 (Figure 3) compares well to those obtained from low-intensity <sup>29</sup>Si satellites in the <sup>1</sup>H NMR spectrum of 3 (<sup>1</sup>J<sub>Si–H</sub> = 196 Hz and <sup>2</sup>J<sub>Si–H</sub> = 20 Hz) and the average <sup>1</sup>J<sub>Si–H</sub> value (195 Hz) observed in the <sup>29</sup>Si NMR spectrum of a “push–pull”-stabilized



**Figure 3.** Proton-coupled <sup>29</sup>Si NMR spectrum of 3. [δ (ppm): for Si(1), a = −26.00, b = −27.96; for Si(2), c = −72.93, d = −73.13].

parent monochlorosilylene [:Si(H)Cl] (5).<sup>56</sup> The Si–H IR stretching band ( $\nu$  = 2109 cm<sup>−1</sup>) for 3 is between that ( $\nu$  = 2103 cm<sup>−1</sup>) for 5 and that ( $\nu$  = 2118 cm<sup>−1</sup>) for L<sub>2</sub>SiH<sub>2</sub>Cl<sub>2</sub> [L: = :C{N(2,6-Pr<sup>i</sup><sub>2</sub>C<sub>6</sub>H<sub>3</sub>)CH}<sub>2</sub>].<sup>57</sup> In addition, the distorted trigonal pyramidal geometry around the Si(2) atom of 3 is consistent with the existence of the Si(2)-based lone pair (Figure S2).<sup>30</sup> Both C(30)–Si(2) [1.941(6) Å] and C(1)–Si(1) [1.909(6) Å] bond distances in 3 are comparable with those [1.929(7)–1.943(2) Å] of the C<sub>NHC</sub>–Si bonds in [L:(X)Si–Si(X):L, X = Cl, Br, and I (2)].<sup>28,29</sup> The S–Si bonds in 3 [2.183(2) and 2.263(2) Å] are somewhat longer than those in Si(SAr)<sub>2</sub> [Ar = C<sub>6</sub>H<sub>3</sub>-2,6(C<sub>6</sub>H<sub>2</sub>-2,4,6-Me<sub>3</sub>)<sub>2</sub>] [2.1560(5) and 2.1607(5) Å].<sup>24</sup>

The X-ray structure<sup>30</sup> of 4 (Figure 4) suggests the insertion of one silylene center into the C(16)–N(1) bond of the

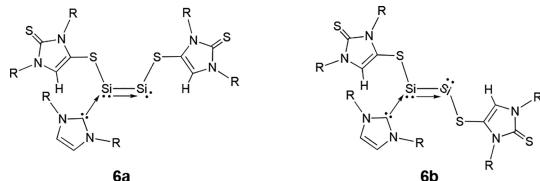


**Figure 4.** Molecular structure of 4. Thermal ellipsoids represent 30% probability. Hydrogen atoms have been omitted for clarity. Selected bond distances (Å) and angles (deg): Si(1)–Si(2), 2.4164(11); Si(1)–C(1), 1.952(3); Si(1)–S(2), 2.2181(11); Si(2)–N(1), 1.838(3); Si(2)–C(16), 1.889(3); C(1)–Si(1)–Si(2), 67.84(9); C(1)–Si(1)–S(2), 100.20(9); N(1)–Si(2)–Si(1), 78.78(9); Si(1)–Si(2)–S(4), 125.49(5); Si(1)–Si(2)–C(16), 126.58(10).

carbene ligand, giving a nonplanar four-membered CNSi<sub>2</sub> silylene ring with two thiolate ligands residing above and below the ring. Indeed, in contrast to only one imidazole <sup>1</sup>H NMR resonance observed for 3 (6.30 ppm), compound 4 exhibits two imidazole <sup>1</sup>H NMR resonances at 5.20 and 6.16 ppm. Similar to 3, the distorted trigonal pyramidal geometry around Si(1) atom in 4 is due to the presence of Si(1)-based lone pair of electrons (Figure S3).<sup>30</sup> The Si–Si bond in 4 is predominantly polarized toward the four-coordinate Si(2) atom [62.9% toward Si(2) and 37.1% toward Si(1) for 4-Ph model (Figure S3)].<sup>30</sup> Although comparable to that in the 4-Ph model (2.463 Å), the Si–Si bond distance in 4 [2.4164(11) Å] is ca. 0.07 Å longer than that in 3 [2.349(2) Å], which is in accordance with the corresponding WBI<sub>Si–Si</sub> values (0.82 for 4-Ph and 0.85 for 3-Ph).<sup>30</sup> The two <sup>29</sup>Si NMR resonances (+2.21 and −56.73 ppm), which are assigned to the four- and three-coordinate silicon atoms [i.e., Si(2) and Si(1)] in 4, respectively, shift downfield compared with the corresponding resonances for 3 [−27.00 ppm for Si(1) and −72.98 ppm for

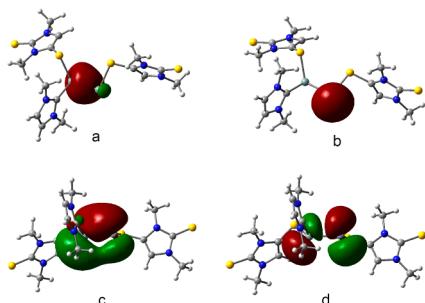
Si(2)] (Figure 3). Both C<sub>NHC</sub>—Si [1.952(3) Å] and S—Si [2.1502(11) and 2.2181(11) Å] bond distances in **4** compares to those for **3** ( $d_{C(1)-Si(1)} = 1.909(6)$  Å,  $d_{S-Si} = 2.183(2)$  and 2.263(2) Å]. Additionally, the Si—N bond distance of **4** [1.838(3) Å] is comparable to the reported Si—N<sub>imidazole</sub> bond distances [1.759(1)–1.837(3) Å]<sup>58,59</sup>

The mechanism of thiolate (**1**)-mediated conversion of bis-silylene (**2**) into two cyclic silylene isomers (**3** and **4**) remains obscured. However, it is plausible to propose **6a** and **6b** (Figure 5), as possible intermediate precursors of **3** and **4**, which could



**Figure 5.** Proposed intermediates (**6a** and **6b**) containing a Si<sub>2</sub><sup>I</sup> unit with an asymmetric Si=Si double bond.

be achieved via double thiolate ligand coordination and subsequent release of one carbene ligand in **2**. The nature of intermediates **6a** and **6b** was investigated by performing B3LYP/6-311G\*\* DFT computations on the simplified models (**6a-Me** and **6b-Me**, R = Me).<sup>30</sup> Computations suggest that both **6a-Me** and **6b-Me** are nearly equal in energy (energy difference = ca. 0.5 kcal/mol). Given their similar structural parameters, only the bonding of **6a-Me** is discussed herein. Interestingly, the silicon–silicon bond distance in **6a-Me** (2.309 Å) is only 0.08 Å longer than the reported Si=Si double bond distance [2.2294(11) Å] in L:Si=Si:L [L: = :C{N(2,6-Pr<sub>2</sub>C<sub>6</sub>H<sub>3</sub>)CH<sub>2</sub>}<sub>2</sub>]<sup>28</sup> and 0.08 Å shorter than the Si—Si single bond in **2** [2.3909(9) Å].<sup>29</sup> The relatively short silicon–silicon bond in **6a-Me**, coupled with the 1.33 Si—Si Wiberg bond index (WBI), suggests that the silicon–silicon bond in **6a-Me** possesses a measure of multiple bond character. NBO analysis of **6a-Me** (Figure 6) shows that the Si—Si  $\sigma$  bonding orbital



**Figure 6.** Natural bond orbitals of the simplified model **6a-Me**. (a) Si—Si  $\sigma$  bonding orbital; (b) silicon-based lone pair orbital; (c) Si—Si  $\pi$  bonding orbital; (d) Si—Si  $\pi^*$  antibonding orbital.

(67.8%) and  $\pi$  bonding orbital (69.9%) are polarized toward the three-coordinate Si(1) atom.<sup>30</sup> While the Si—Si  $\pi$  bonding orbital (Figure 6c) has overwhelmingly p-character [99.2% p of Si(1) and 94.7% p of Si(2)], the Si—Si  $\sigma$  bonding orbital (Figure 6a) involves the overlap of the approximately sp-hybridized Si(1) atomic orbital (47.2% s, 52.5% p, 0.3% d) with the Si(2) atomic orbital bearing mostly p-character (8.8% s, 90.3% p, 0.9% d). Moreover, the two-coordinate Si(2)-based lone pair orbital (Figure 6b) has mainly s-character (77.5% s,

22.5% p, 0.0% d). Considering that two-coordinate acyclic silylenes have been utilized in H<sub>2</sub>, O<sub>2</sub>, and NH<sub>3</sub> activation,<sup>26,27</sup> the presence of two different types of reactive sites in both **6a** and **6b** intermediates (i.e., asymmetric and polarized Si=Si double bond and the two-coordinate acyclic silylene center) could play a role in the unexpected C—H and C—N cleavage involved in the formation of **3** and **4**, respectively.

## ASSOCIATED CONTENT

### Supporting Information

The Supporting Information is available free of charge on the ACS Publications website at DOI: 10.1021/jacs.7b10325.

Syntheses, computations, X-ray crystal determination (PDF)

Crystallographic data for **3** (CIF)

Crystallographic data for **4** (CIF)

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### Notes

The authors declare no competing financial interest.

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